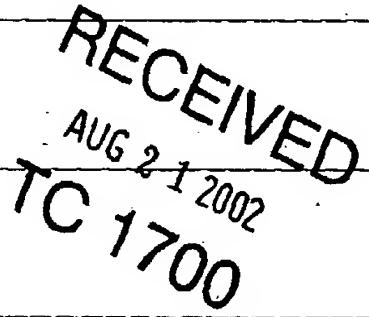


INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>			Docket Number (Optional) YPL-0026		Application Number 10/086,496	
			Applicant(s) GEUN-YOUNG YEOM, ET AL.		Filing Date February 28, 2002	
U.S. PATENT DOCUMENTS						
EXAMINER INITIALS <i>J.C.</i>	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>COPY OF PAPERS ORIGINALLY FILED</i>						
FOREIGN PATENT DOCUMENTS						
REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation
						YES
<i>RECEIVED AUG 21 2002 TC 1700</i>						
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<i>dme</i>	D.B. Oaks, W.G. Lawrence and A.H. Gelb, "Selective, Anisotropic and Damage-Free SiO ₂ Etching with a Hyperthermal Atomic Beam", Physical Sciences Inc., 20 New England Business Center, Andover, MA 01810, 7 pages					
<i>dme</i>	M.J. Goeckner, T.K. Bennett, Jaeyoung Park, Z. Wang and S.A. Cohen, "Reduction of Residual Charge in Surface-Neutralization-Based Neutral Beams", 1997 2nd Int'l Symposium on Plasma Process-Induced Damage; May 13-14, pages 175-178					
EXAMINER <i>John Mitchell Howell</i>	DATE CONSIDERED <i>03-10-04</i>					

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>		Docket Number (Optional) 10/086,496	Application Number YPL-0026
		Applicant(s) GEUN-YOUNG YEOM, ET AL.	
		Filing Date February 28, 2002	Group Art Unit
*EXAMINER INITIAL <i>a.mg</i>	OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>		
<p>B.A. Helmer and D.B. Graves "Molecular dynamics simulations of Cl₂ impacts onto a chlorinated silicon surface: Energies and angles of the reflected Cl₂ and Cl fragments", J.Vac. Sci. Technol. A 17(5), Sep/Oct 1999, pages 2759 -2770</p> <p><i>OIE JC JUN 12 2002 PATENTS</i></p> <p>Takashi Yunogami, Ken'etsu Yokogawa, and Tatsumi Mizutani, "Development of neutral-beam-assisted etcher", J.Vac. Sci. Technol. A 13(3), May/June 1995, pages 952 - 958</p>			
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EXAMINER <i>A. Mitchell Gowell</i>	DATE CONSIDERED <i>03-10-02</i>		

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.